

ABATEMENT SYSTEM FOR CLF3 CONTAINING EXHAUST GASES

ABSTRACT

The invention relates to a process for the abatement of a ClFx containing gas such as exhaust gases from a reactor wherein at least one step of the manufacture of integrated circuit is carried out, wherein said ClFx containing gas is passed through a bed of adsorbent comprising sodalime which moisture content is less than 3% weight, to substantially remove all of the ClFx compound from said ClFx containing gas with substantially no generation of byproduct.

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